

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention

HIGH-PRESSURE PROCESSING CHAMBER FOR A
SEMICONDUCTOR WAFER

Application Number : 10/680783
Confirmation Number: 5859
First Named Applicant: William Jones
Attorney Docket Number:
Art Unit:
Examiner:
Search string: (5494526 or 6333268).pn



Certification: This Information Disclosure Statement was submitted under the following conditions, which satisfies the requirement under 37 CFR 1.97(e). The filer certified:

That no item of information contained in the information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application, and, to the knowledge of the person signing the certification after making reasonable inquiry, no item of information contained in the information disclosure statement was known to any individual designated in 37 CFR 1.56(c) more than three months prior to the filing of the information disclosure statement.

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
	1	5494526	1996-02-27	Paranjpe			
	2	6333268	2001-12-25	Starov et al.	B1		

Signature

Examiner Name	Date